

Notice of References Cited	Application/Control No. 10/713,217	Applicant(s)/Patent Under Reexamination ENDO ET AL.	
	Examiner Kathleen Duda	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2002/0163629	11-2002	Switkes et al.	355/53
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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	N					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Hoffnagle et al., "Liquid Immersion Deep-ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B 17(8), Nov/Dec 1999, pp.3306-3309.
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	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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